



Microprocessor-Controlled Spin Coater SCC-200

- Rotational speed up to 12.000 rpm
- Two rotational speed ramps
- Programmable ramp duration: 3 s .. 600 s
- Two rotational speed target values
- Programmable dwell time: 3 s .. 600 s
- Alphanumeric four-line display (20 characters/line)
- 10 rotational speed sequences storable in non-volatile memory
- Display of remaining processing time
- Total process times: 12 s .. 40 minutes
- Active vacuum suction of the sample
- Film thickness range 10 nm to 10 μ m
- Easy-to-use and maintenance free design
- Rotational platforms for substrates up to 90 mm diameter

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SCC-200

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Our microprocessor-controlled spin coater SCC-200 helps you prepare thin films easily within a few minutes. Films are produced on a substrate that is fixed to an exchangeable rotational platform by a pump-generated underpressure.

Both circular and rectangular substrates up to 90 mm diameter can be placed on the rotational platform (various sizes available, see the accessories list).

The resulting film thickness merely depends on the solid/solvent concentration, rotational speed, and time.

The ergonomic design makes the SCC-200 spin coaters an efficient tool for the preparation of thin films of both organic and inorganic substances for microscopic or spectroscopic investigations.

Spin coating using the SCC-200 neither requires specific skills nor prior experience and is maintenance free.



During operation, a built-in digital four-line display with 20 characters per line informs about the rotation speed and the remaining ramp or dwell times for testing under reproducible conditions. It also substantially facilitates the set-up of the spin coater. For the sake of reproducibility, 10 programming sequences can be stored permanently in the SCC-200 non-volatile memory. These programmes consist of two rotational speeds up to 200 rps (12.000 rpm), ramp times, and dwell times, respectively. The latter may be varied over a wide range, i.e., between 3 s and 600 s, providing substantial flexibility to the spin coating process with total process times between 12 s and 40 minutes. Operating and setting up the SCC-200 is easily performed by single-knob control. Using the SCC-200, thin and ultra thin layers of extraordinary homogeneity are easily achieved.

As a high quality product, this spin coater comes with 2 years guarantee.

Accessories for the SCC-200

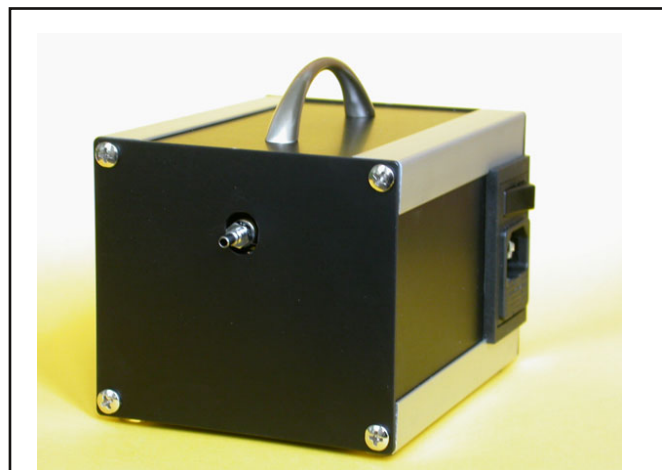
- Vacuum pump MVP with hose and quick coupling (highly recommended)
- VT-25P rotational platform (plane chuck; Ø 25 mm, for small and irregularly shaped substrates)
- VT-30 rotational platform (Ø 30 mm)
- VT-50P rotational platform (plane chuck; Ø 50 mm) (discontinued)
- VT-50 rotational platform (Ø 50 mm)
- VT-70 rotational platform (Ø 70 mm)
- VT-90 rotational platform (Ø 90 mm)

All rotational platforms are made of aluminium.

Regular platforms are equipped with small channels on their surface to ensure uniform pressure on the substrate.

Plane platforms lack these channels; evacuation is performed exclusively through the center hole. This arrangement is better suited for small or irregularly shaped substrates that would leave major parts of the channel structure uncovered.

The SCC-200 comes with a switching power supply and a VT-30 rotational platform.



Small Vacuum Pump MVP

- Underpressure of -33,3 kPa
- Flow of 7 litres/min
- Max. 40 dB(A) noise

Note: exact appearance may vary.